



SIXTH SEMESTER B.TECH. (INSTRUMENTATION & CONTROL ENGG.)

END SEMESTER EXAMINATIONS, JUNE 2017

SUBJECT: MICRO ELECTRO MECHANICAL SYSTEMS [ICE 4010]

Time: 3 Hours

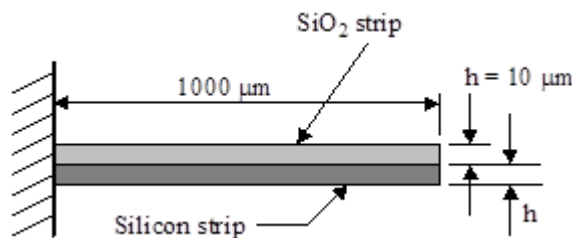
MAX. MARKS: 50

Instructions to Candidates:

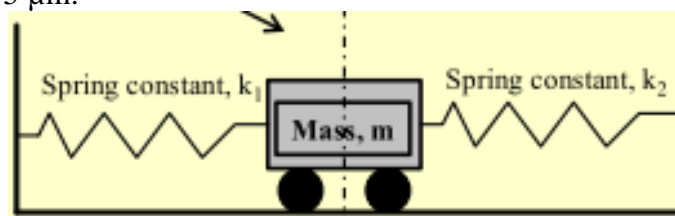
- ❖ Answer **ALL** questions.
- ❖ Missing data may be suitably assumed.

- 1A. Write a note on the characteristics of MEMS. 4
- 1B. Explain why silicon is preferred in micro fabrication and the process of silicon growth from the melt in detail. 6
- 2A. Implement the following logic using CMOS technology. 4

$$Y = \overline{A.B} \overline{C.D}$$
- 2B. List the steps involved in the fabrication of microelectronic ICs. 2
- 2C. Calculate and compare the maximum deflection and stress of a circular and square diaphragm pressure sensor with an area of $196250 \mu\text{m}^2$ and thickness of $60 \mu\text{m}$ for an applied pressure of 50MPa. Young's modulus of silicon is 190 GPa and poisson's ratio is 0.27. 4
- 3A. A bi-layer strip is subjected to a uniform temperature rise, T as illustrated below. Calculate the radius of curvature and deflection at the free end for a temperature of 70°C . Consider $E_{\text{SiO}_2} = 385\text{GPa}$, $E_{\text{Si}} = 190\text{GPa}$ and $\alpha_{\text{SiO}_2} = 0.5 \times 10^{-6} / ^\circ\text{C}$, $\alpha_{\text{Si}} = 2.33 \times 10^{-6} / ^\circ\text{C}$. 4

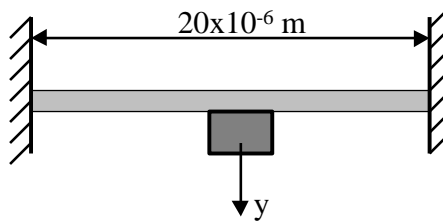


- 3B. Determine the amplitude and frequency of vibration of a 20-mg mass attached to two springs as shown in the figure. The spring constants are $k_1 = 5 \times 10^{-5} \text{ N/m}$ and $k_2 = 8 \times 10^{-5} \text{ N/m}$. The vibration begins with the mass being pulled to the right with an amount of $\delta_{\text{st}} = 5 \mu\text{m}$. 4

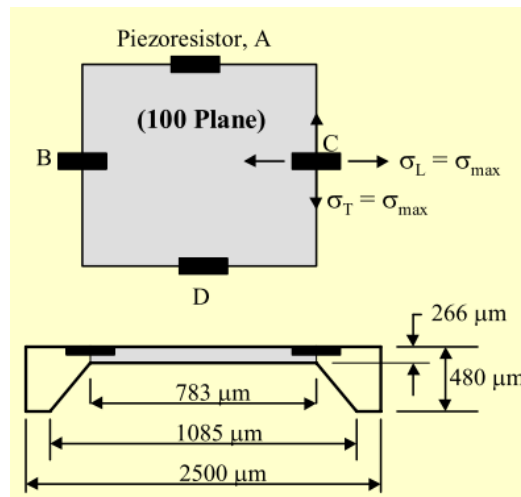


3C. Explain the working of a bio sensor. 2

4A. A micro device component 5g in mass is attached to a fine strip made of silicon as shown in figure. The equivalent beam spring constant k_{eq} is 18240 N/m. The mass is pulled down by 5 μm initially and is released at rest. Determine (a) the natural frequency of the device and the maximum amplitude of vibration. 3

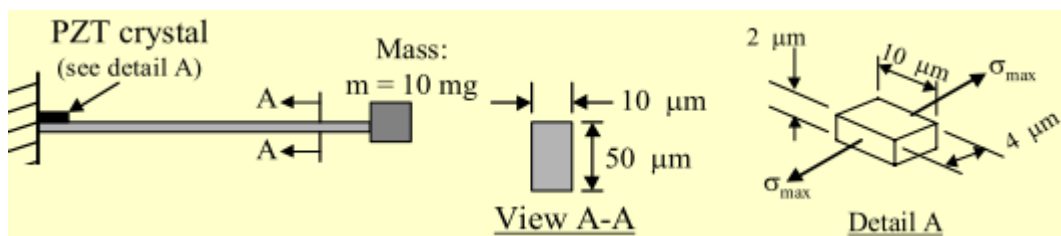


4B. Estimate the change of resistance in silicon piezoresistors attached to the diaphragm of a pressure sensor as shown below for an applied pressure of 50MPa. Consider E as 190GPa and $\pi_{44} = 138.1 \times 10^{-11} \text{ Pa}^{-1}$. 4



4C. Write a note on epitaxial growth. 3

5A. A thin piezoelectric crystal film, PZT is used to transduce the signal in a micro accelerometer involving a cantilever beam made of silicon. The accelerometer is design for maximum acceleration/deceleration of 10 g. The dimensions are $L=800\mu\text{m}$, $b=50\mu\text{m}$ and $t= 10\mu\text{m}$. Calculate the voltage generated by the PZT. The piezoelectric coefficient of the crystal film is $2.3\text{e-}12 \text{ m/V}$. 5



5B. Explain the process of etching and its classification. 3

5C. Write a short note about lift-off technique. 2